

## Supporting Information

### Nitrogen-Rich Molybdenum Nitride Synthesized in a Crucible under Air

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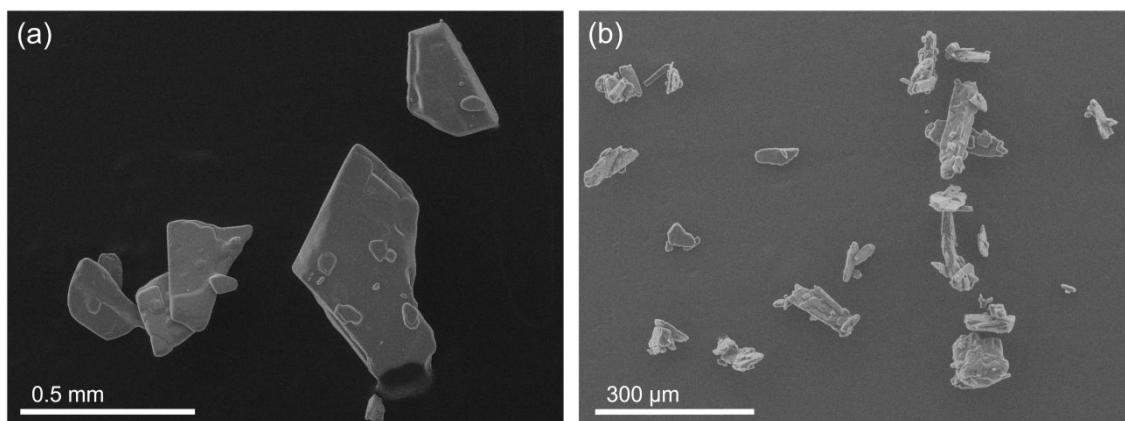
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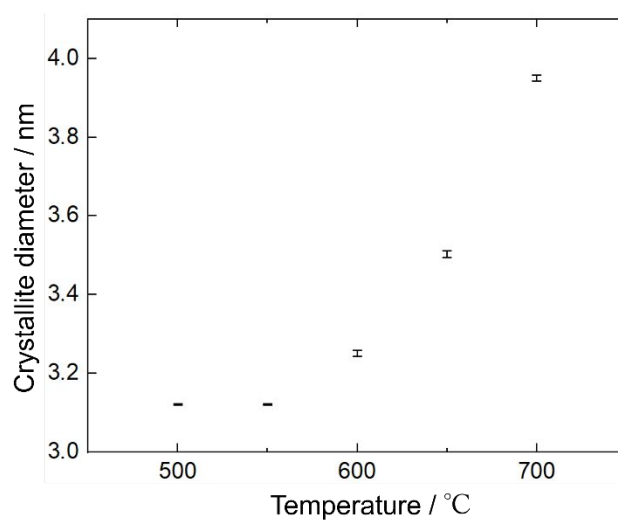
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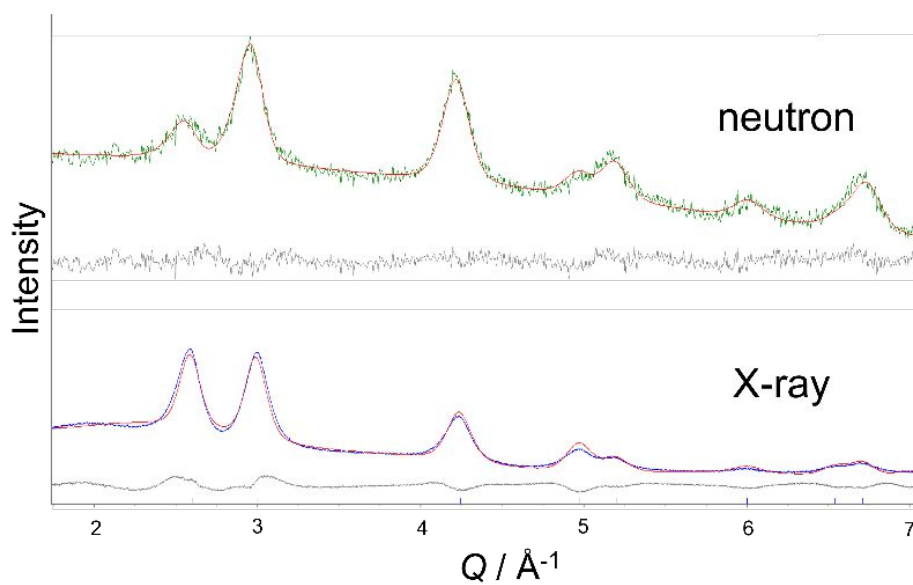
**Figure S1. SEM image of starting materials, (a)Na<sub>2</sub>MoO<sub>4</sub>·2H<sub>2</sub>O, (b) dicyandiamide (C<sub>2</sub>N<sub>4</sub>H<sub>4</sub>).**



**Figure S2. Dependence of synthesis temperature and crystalline size of Mo<sub>2</sub>N<sub>3</sub> determined by Scherrer equation.**

**Table S1. Simultaneous analysis results of XRD and neutron diffraction of the product synthesized at 600 °C.**

<b>Lattice / Å</b>	4.186(13)
<b>Occ. Mo</b>	0.577(6)
<b>Occ. N</b>	0.996(5)
<b><math>R_{wp}/\%</math></b>	3.4678



**Figure S3. Simultaneous analysis profile of XRD and neutron diffraction of the product synthesized at 600 °C**

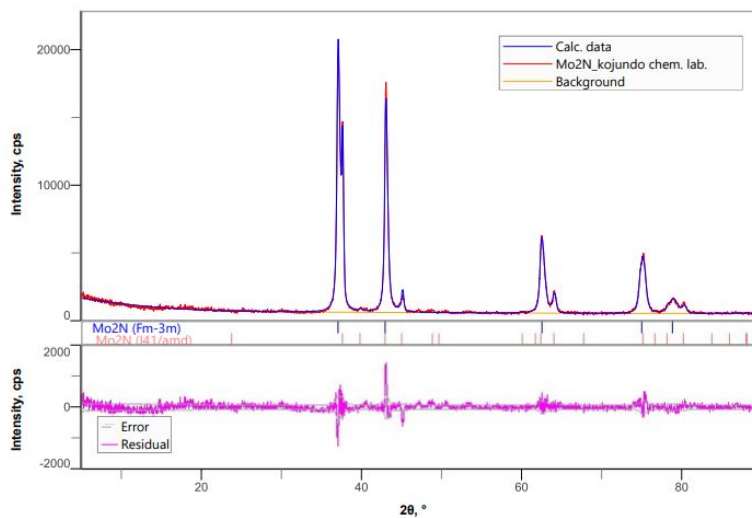
**Table S2. Hypothetical Na substitution effect on the lattice constants and occupancies of the product synthesized at 600 °C.**

**XRD**

	<b>Na 0</b>	<b>Na 0.1</b>	<b>Na 0.2</b>
<b>Lattice / Å</b>	4.1991(3)	4.1991(3)	4.1991(3)
<b>Occ. Mo</b>	0.672(19)	0.645(2)	0.620(2)
<b>Occ. N</b>	1	1	1
<b>Occ. Na</b>	0	0.1	0.2
<b><math>R_{wp}/\%</math></b>	1.230	1.226	1.229
<b><math>S</math></b>	0.4041	0.4031	0.4039

**ND**

	<b>Na 0</b>	<b>Na 0.1</b>	<b>Na 0.2</b>
<b>Lattice / Å</b>	4.1991	4.1991	4.1991
<b>Occ. Mo</b>	0.672	0.645	0.620
<b>Occ. N</b>	1	1	0.3934
<b>Occ. O</b>	0	0	0.6066
<b>Occ. Na</b>	0	0.1	0.2
<b><math>R_{wp}/\%</math></b>	2.51	2.715	4.264
<b><math>S</math></b>	1.5848	1.7065	1.6465



**Figure S4.** Rietveld refinement of  $\text{Mo}_2\text{N}$  used as a standard of XANES analysis. Brack line is experimental value, red one is calculated date, and blue one is residual value.

**Table S3.** Rietveld analysis results of  $\text{Mo}_2\text{N}$  used in XANES.

	$\text{Mo}_2\text{N} (Fm\bar{3}m)$	$\text{Mo}_2\text{N}(I4_1/amd)$
$a/\text{\AA}$	4.2051(4)	4.2102(6)
$b/\text{\AA}$	4.2051(4)	4.2102(6)
$c/\text{\AA}$	4.2051(4)	8.0445(11)
<b>Occ. Mo</b>	1	1
<b>Occ. N</b>	0.734(13)	0.54(5)
<b>Mass %</b>	74.4(2)	25.6(2)

**Figure S4.** Details of the  $\text{Ar}^+$  etching channel used.

<b>Beam energy (eV)</b>	3000
<b>Emis current (mA)</b>	20
<b>Gas Pressure (Pa/<math>10^2</math>)</b>	9.5
<b>Etching rate (nm <math>\text{min}^{-1}</math>)</b>	6.0